

Title (en)

Apparatus for processing a work piece with a uniformly neutralised ion beam

Title (de)

Apparat zur Bearbeitung eines Werkstücks mit einem gleichmässig neutralisierten Ionenstrahl

Title (fr)

Appareil pour le traitement d'une cible par un faisceau d'ions uniformement neutralisé

Publication

EP 0964425 A3 20040211 (EN)

Application

EP 99110048 A 19990521

Priority

JP 16027198 A 19980609

Abstract (en)

[origin: EP0964425A2] In order to uniformly neutralize a large current and a large diameter ion beam so as to irradiate an ion beam having a reduced beam divergence on a process target. An ion beam processing apparatus comprises an ion source (1) with an extraction electrode (6,9), a processing chamber (13) for accommodating a process target (27), and an annular microwave neutralizer (14) with an annular electrode (47) disposed around the ion beam. <IMAGE>

IPC 1-7

H01J 27/18; **H01J 37/08**

IPC 8 full level

H05H 1/46 (2006.01); **B23K 15/00** (2006.01); **C23F 4/00** (2006.01); **H01J 27/18** (2006.01); **H01J 37/08** (2006.01); **H01L 21/302** (2006.01); **H01L 21/3065** (2006.01)

CPC (source: EP US)

H01J 27/18 (2013.01 - EP US); **H01J 37/08** (2013.01 - EP US); **H01J 2237/0041** (2013.01 - EP US); **H01J 2237/0817** (2013.01 - EP US); **H01J 2237/3142** (2013.01 - EP US)

Citation (search report)

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- [A] EP 0443154 A2 19910828 - HITACHI LTD [JP]
- [A] US 5518572 A 19960521 - KINOSHITA OSAMU [JP], et al

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DE10024883A1

Designated contracting state (EPC)

AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

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EP 99110048 A 19990521; JP 16027198 A 19980609; US 32750299 A 19990608; US 75066501 A 20010102